

20th European Wet & 49th European CMP Users Meeting

Wet- and CMP-Session: Thursday, November 27, 2025, 12:30 – 17:40

CMP-Session: Friday, November 28, 2024, 2025, 8:30 – 13:15

Abbaey Royaumont, Asnières sur Oise, France

Organized by European CMP&WET Usergroup & supported by Technic France

Agenda Thursday, November 27th

12:30 – 13:45 Welcome Coffee, Tea, Softdrinks and Light Lunch

13:45 Opening Remarks & Welcome

Knut Gottfried

Fraunhofer ENAS & ErzM-Technologies, Chemnitz, Germany

Wet Session

Session Chair: Knut Gottfried, Fraunhofer ENAS & ErzM-Technologies, Chemnitz, Germany

13:50 A Comparative Study of Single-Wafer Megasonic Cleaning Systems

Kazuaki Arai

Kaijo Shibuya Europe, Heidelberg, Germany

14:05 ACE by RENA: First SiC Wet Etching

Martin Pretscher¹, Norbert Bay¹, Athul Rathnakar², Xavier Gay¹, Wyatt Engler¹, Rahim Hamid¹, Franck Delahaye¹, Oliver Whear¹, Vishal A. Shah², and Holger Kuehnlein¹

¹RENA Technologies GmbH, Guetenbach, Germany, ²School of Engineering, University of Warwick, Coventry, UK

14:20 AP&S FlowSim – The way to tune your processes

Stefan Zürcher and Simon Gräfner

AP&S, Donaueschingen, Germany

14:35 From Reactive to Responsive: Mechanochemical Pathways for Stimuli-Activated Surface Cleaning

Jason Keleher

Lewis University, Romeoville, IL, USA

15:00 Wet Processes for Advanced Packaging Technologies

Harold le Tulzo, Marine Audouin, Diane Bijou, Rogelio J. Gomez Pineiro, Loriane Celeste, Anaïs Passelande, Gaël Galantine, Audrey Valette, Jérôme Daviot

Technic France, La Plaine Saint Denis, France

15:25 **Coffee Break**

CMP Session 1: CMP Processes and Tutorial CMP

Session Chair: Gerfried Zwicker, zwickerconsult, Berlin, Germany

16:00 CMP development for Ultra-Scaled Back-End TiN Contacts for High Density Memory Applications

Floriane Baudin

CEA Leti, Grenoble, France

- 16:15 ARS Study on Polished Wafers
Boris Brodmann², Etienne Babnik¹, and Ara Philipossian³
¹NanoFocus GmbH, Oberhausen, Germany, ²OptoSurf GmbH, Ettlingen, Germany, ³Araca Inc., Tucson, AZ, USA
- 16:45 **Tutorial:** Advanced CMP Applications
Federico Barbieri
Entegris/CMC Materials, Barry / Vale of Glamorgan, UK
- 17:35 Trainee Mentoring Programm
Catharina Rudolph
Fraunhofer ASSID, Dresden, Germany
- 17:40 End of Wet Users Meeting / time for networking and discussion
- 18:30 Champagne reception, sponsored by Technic France
- 19:00 Workshop Dinner at Abbey Royaumont

Agenda Friday, November 28th

- 8:30 – 9:00 Good Morning Coffee, Tea, Softdrinks
- 9:00 Opening Remarks
Martin Kulawski
Advaplan, Espoo, Finland
- CMP Session 2: CMP Processes**
Session Chair: Martin Kulawski, Advaplan, Espoo, Finland
- 9:05 Tuning Interfacial Reactions for Low-Stress and Self-Cleaning CMP Performance
Jason Keleher
Lewis University, Romeoville, IL, USA
- 9:30 Dishing Dependency on Polishing Pressure and Time – STI CMP
Awwal Adesunkanmi and Andreas Krüger
Leibniz Institute for High Performance Microelectronics, Frankfurt/Oder, Germany
- 9:45 Impact of Sub-Optimal *In-Situ* Pad Conditioning Recipes on Process Vibrations in Copper CMP
Ara Philipossian, Yasa Sampurno, and Leonard Borucki
Araca Inc., Tucson, AZ, USA
- 10:10 CMP modelling for mask design and process improvement at imec
Karl Ceulemans, Kevin Vandersmissen, Catarina Regra Da Silva, and Juergen Boemmels
Imec, Leuven, Belgium
- 10:25 Exploring the Potential of Machine Learning in Developing CMP Slurry Composition
Akihiro Orita
Resonac, Hitachi, Japan
- 10:50 **Coffee Break**

CMP Session 3: CMP Processes

Session Chair: Catharina Rudolph, Fraunhofer IZM-ASSID, Dresden, Germany

- 11:30 Emblem™ Pads: Next-gen High Performance Pads and Costumers Success
Ricardo Duyos Mateo, Olivier Cesbron, and Michael Hauck
Qnity Electronics, Wilmington, Delaware, USA
- 11:55 From Filtration to Planarisation: A D2W CMP Consumable Set Evaluation
Clément Castan and Victor Soty
CEA Leti, Grenoble, France
- 12:20 Evolution, Roadmap, and Future Opportunities of Automated Atomic Force Microscope
Ryan Yoo
Park Systems GmbH, Mannheim, Germany
- 12:45 Controlling CMP and Grinding Processes in the Semiconductor Industry
Samuel Seignovert
Precitec France, Chateauneuf-le-rouge, France
- 13:00 Highlights from ICPT 2025
Gerfried Zwicker
zwickerconsult, Berlin, Germany
- 13:15 End of CMP Users Meeting / time for networking and discussion
Coffee, Tea, Softdrinks, Snacks and Light Lunch